OTPE 12006 JAN 27 2006

EFRADE

PTO/SB/08A (08-03)

Approved for use through 07/31/2006. OMB 0651-0031
Patent and Trademark Office U.S. DEPARTMENT OF COMMERCE

U.S. Patent and Trademark Office, U.S. DEPARTMENT OF COMMERCE Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number

Substitute for form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Sheet	1	of	1

Complete if Known /				
Application Number	10/564,170			
Filing Date	January 10, 2006			
First Named Inventor	Volker Krink, et al			
Art Unit	TBD			
Examiner Name	TBD			
Attorney Docket Number	51034.0000			

U.S. PATENT DOCUMENTS

Patent or Publication Number	Issue or Publication Date	Patentee or Applicant	Class	Subclass
6,232,575	5/15/2001	Oakley, Thomas F., et al	219	121.55
6,359,251	3/19/2002	Picard, Tate S., et al	219	121.57
				<u> </u>
	6,232,575	6,232,575 5/15/2001	6,232,575 5/15/2001 Oakley, Thomas F., et al	6,232,575 5/15/2001 Oakley, Thomas F., et al 219

		FOREIGN PATENT I	DOCUMENTS		
Examiner Initials*	Foreign Patent Document No.	Issue or Publication Date	Patentee or Applicant	Country	
	10263827	10/6/1998	Yashuiro, Asami	JAPAN	
	EP 0 697 935	4/21/1999	Couch, R., et al	EUROPE	
			Weizel, G., et al ontrol of a plasma torch. Gas f e sensor and a shield in the p		
	cutting with high exit speed	of the plasma jet. In front of a eld. This does not solve the pr	g a working gas and an addition gas discharge chamber, a pre oblem that gas mixtures cann	essure drop is	
	DD 132247		Fronlich, H.	GERMANY	
	Description: A method is dis hypersonic nozzles. Howeve	sclosed for mixing of gases. F er, varying optimum mixing ra	or example, for plasma cutting tios required cannot be product	g and using ced.	
	which the volume flow of the supplying a plasma torch wi control means controls the volume flow control alone	egas, mixed gas, or gas mixto th a gas or mixed gas or gas volume flow of the gas or n does not allow for adequate	a torch with a gas, mixed gas, ure is controlled. An arrangem mixture to the plasma torch a nixed gas or gas mixture. Ho a quality of cutting, and can ss, and major deviations in a	ent is provided for and a volume flow wever, the use of lead to unreliable	

	·		
•	1	1	
•		ŀ	
Cuaminas		ľ	
Examiner			
		l	
Signature	l	Date Considered	
	L	 Date Considered	<u> </u>

This collection of information is required by 37 CDR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 USC 122 and 37 CFR 1.14. this collection is estimated to take 2 hours to complete, including gathering, preparing and submitting the completed application form to the USPTO. Time will vary depending on the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should b sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450 DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.